

L Number	Hits	Search Text	DB	Time stamp
2	1952	(gate with oxide) same polysilicon same silicide same nitride	USPAT; US-PGPUB	2004/06/17 14:54
3	1144	(gate adj oxide) same polysilicon same silicide same nitride	USPAT; US-PGPUB	2004/06/17 14:55
5	58	((gate adj oxide) same polysilicon same silicide same nitride) and ((spacers with oxide) same temperature)	USPAT; US-PGPUB	2004/06/17 14:56
6	57	((gate adj oxide) same polysilicon same silicide same nitride) and ((spacers with oxide) same temperature)) and @ad<20021031	USPAT; US-PGPUB	2004/06/17 17:08
10	278	gate and (oxidizing same spacers same oxide) and @ad<20021031	USPAT; US-PGPUB	2004/06/17 15:13
11	3	(gate and (oxidizing same spacers same oxide) and @ad<20021031) and (oxygen same inert same oxidizing) and @ad<20021031	USPAT; US-PGPUB	2004/06/17 17:08
12	1379	gate and ((thermal or rapid) same spacers same oxide) and @ad<20021031	USPAT; US-PGPUB	2004/06/17 15:13
13	14	(gate and ((thermal or rapid) same spacers same oxide) and @ad<20021031) and (oxygen same inert same (thermal or rapid)) and @ad<20021031	USPAT; US-PGPUB	2004/06/17 15:14
14	2019	gate with oxide with polysilicon with silicide	USPAT; US-PGPUB	2004/06/17 17:39
15	8	(gate with oxide with polysilicon with silicide) same sidewall same (thermal or thermally or rapid or oxidize or oxidizing or oxidation) same (inert or argon or nitrogen)	USPAT; US-PGPUB	2004/06/17 17:06
16	7	((gate with oxide with polysilicon with silicide) same sidewall same (thermal or thermally or rapid or oxidize or oxidizing or oxidation) same (inert or argon or nitrogen)) and @ad<20021031	USPAT; US-PGPUB	2004/06/17 17:07
17	265	(gate with oxide with polysilicon with silicide) and (sidewall or spacers) and ((thermal or thermally or rapid or oxidize or oxidizing or oxidation) same (inert or argon or nitrogen))	USPAT; US-PGPUB	2004/06/17 17:40
18	247	((gate with oxide with polysilicon with silicide) and (sidewall or spacers) and ((thermal or thermally or rapid or oxidize or oxidizing or oxidation) same (inert or argon or nitrogen))) and @ad<20021031	USPAT; US-PGPUB	2004/06/17 17:07
19	240	((gate with oxide with polysilicon with silicide) and (sidewall or spacers) and ((thermal or thermally or rapid or oxidize or oxidizing or oxidation) same (inert or argon or nitrogen))) and @ad<20021031 not (((gate with oxide with polysilicon with silicide) same sidewall same (thermal or thermally or rapid or oxidize or oxidizing or oxidation) same (inert or argon or nitrogen)) and @ad<20021031)	USPAT; US-PGPUB	2004/06/17 17:08
20	232	((gate with oxide with polysilicon with silicide) and (sidewall or spacers) and ((thermal or thermally or rapid or oxidize or oxidizing or oxidation) same (inert or argon or nitrogen))) and @ad<20021031 not (((gate with oxide with polysilicon with silicide) same sidewall same (thermal or thermally or rapid or oxidize or oxidizing or oxidation) same (inert or argon or nitrogen)) and @ad<20021031)) not (((gate adj oxide) same polysilicon same silicide same nitride) and ((spacers with oxide) same temperature)) and @ad<20021031)	USPAT; US-PGPUB	2004/06/17 17:08

21	232	((((gate with oxide with polysilicon with silicide) and (sidewall or spacers) and ((thermal or thermally or rapid or oxidize or oxidizing or oxidation) same (inert or argon or nitrogen))) and @ad<20021031) not (((gate with oxide with polysilicon with silicide) same sidewall same (thermal or thermally or rapid or oxidize or oxidizing or oxidation) same (inert or argon or nitrogen)) and @ad<20021031)) not (((gate adj oxide) same polysilicon same silicide same nitride) and ((spacers with oxide) same temperature)) and @ad<20021031)) not ((gate and (oxidizing same spacers same oxide) and @ad<20021031) and (oxygen same inert same oxidizing) and @ad<20021031))	USPAT; US-PGPUB	2004/06/17 17:08
22	232	((((gate with oxide with polysilicon with silicide) and (sidewall or spacers) and ((thermal or thermally or rapid or oxidize or oxidizing or oxidation) same (inert or argon or nitrogen))) and @ad<20021031) not (((gate with oxide with polysilicon with silicide) same sidewall same (thermal or thermally or rapid or oxidize or oxidizing or oxidation) same (inert or argon or nitrogen)) and @ad<20021031)) not (((gate adj oxide) same polysilicon same silicide same nitride) and ((spacers with oxide) same temperature)) and @ad<20021031)) not ((gate and (oxidizing same spacers same oxide) and @ad<20021031) and (oxygen same inert same oxidizing) and @ad<20021031)) not ((gate and ((thermal or rapid) same spacers same oxide) and @ad<20021031) and (oxygen same inert same (thermal or rapid)) and @ad<20021031))	USPAT; US-PGPUB	2004/06/17 17:09
23	59	((((gate with oxide with polysilicon with silicide) and (sidewall or spacers) and ((thermal or thermally or rapid or oxidize or oxidizing or oxidation) same (inert or argon or nitrogen))) and @ad<20021031) not (((gate with oxide with polysilicon with silicide) same sidewall same (thermal or thermally or rapid or oxidize or oxidizing or oxidation) same (inert or argon or nitrogen)) and @ad<20021031)) not (((gate adj oxide) same polysilicon same silicide same nitride) and ((spacers with oxide) same temperature)) and @ad<20021031)) not ((gate and (oxidizing same spacers same oxide) and @ad<20021031) and (oxygen same inert same oxidizing) and @ad<20021031)) not ((gate and ((thermal or rapid) same spacers same oxide) and @ad<20021031) and (oxygen same inert same (thermal or rapid)) and @ad<20021031)) and (oxygen with (inert or argon or nitrogen))	USPAT; US-PGPUB	2004/06/17 17:10
24	622	gate with oxide with polysilicon with silicide	EPO; JPO; DERWENT; IBM_TDB	2004/06/17 17:39
25	11	(gate with oxide with polysilicon with silicide) and (sidewall or spacers) and ((thermal or thermally or rapid or oxidize or oxidizing or oxidation) same (inert or argon or nitrogen))	EPO; JPO; DERWENT; IBM_TDB	2004/06/17 17:40